



**SW Test Workshop**  
Semiconductor Wafer Test Workshop

# A Full-Automatic Test System for Characterizing Large-Array Fine-Pitch Micro-Bump Probe Cards

Erik Jan Marinissen

Ferenc Fodor

Bart De Wachter



Leuven, Belgium

Jörg Kieseewetter

Thiendorf, Germany

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Eric Hill

Ken Smith



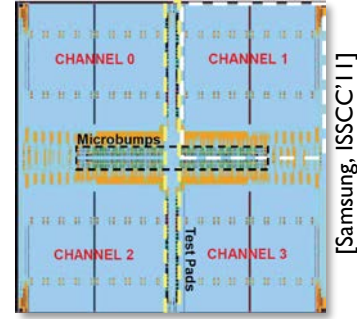
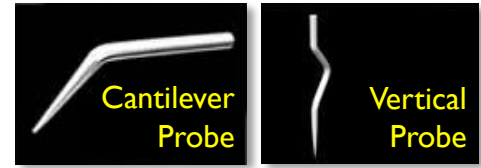
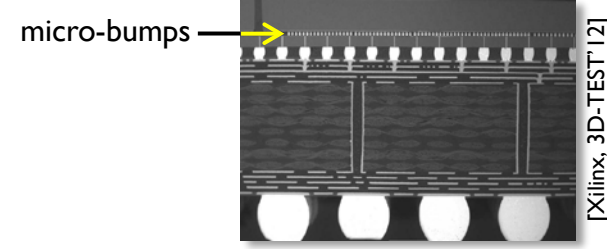
**CascadeMicrotech**<sup>®</sup>

A FORMFACTOR COMPANY

Beaverton, OR, USA

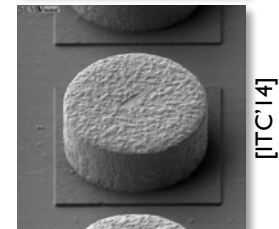
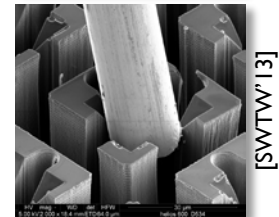
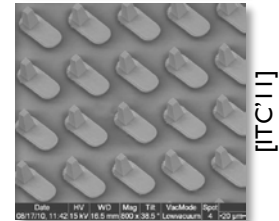
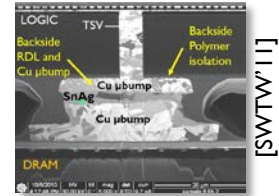
# Direct Micro-Bump Probing

- Functional interconnects of 3D-stacked dies are formed by large arrays of fine-pitch micro-bumps
- Impossible to probe with conventional probe technology
  - Cantilever probes : cannot handle arbitrary arrays
  - Vertical probes : cannot handle the fine pitch
- Options for pre-bond test
  1. Skip pre-bond test: poor compound stack yield; higher cost
  2. Dedicated pre-bond probe pads: extra design, area, test time, post-bond load; and micro-bumps remain untested
  - ➔ **3. Use advanced probe technology to probe micro-bumps**



## Related Prior Work

- **SWTW'11:** Marinissen et al. (*imec + Cascade Microtech*)  
Imec and Cascade started collaboration, defined probe targets
- **ITC'11:** Smith et al. (*Cascade Microtech + imec*)  
First collaboration results, mainly on probe technology
- **SWTW'13:** Böhm et al. (*Feinmetall + Team Nanotec + imec + FH + CM*)  
Silicon crown tips, embedded in vertical probe card with TSVs  
**Most Inspirational Presentation Award**, but no product follow-up
- **ITC'14:** Marinissen et al. (*imec + Cascade Microtech + TU Delft*)
  - WIOI-1Bank: good  $R_C$ ; no impact on bond yield; cost-effective
  - But... (i) only 1 Bank and (ii) only daisy-chains of 30 micro-bumps



# Presentation Overview

1. Introduction
2. Wide-I/O Micro-Bump Arrays
3. Vortex-2 Test System
4. Probe Technology
5. Test System Software
6. Experimental Results
7. Test Cost Comparison
8. Conclusion

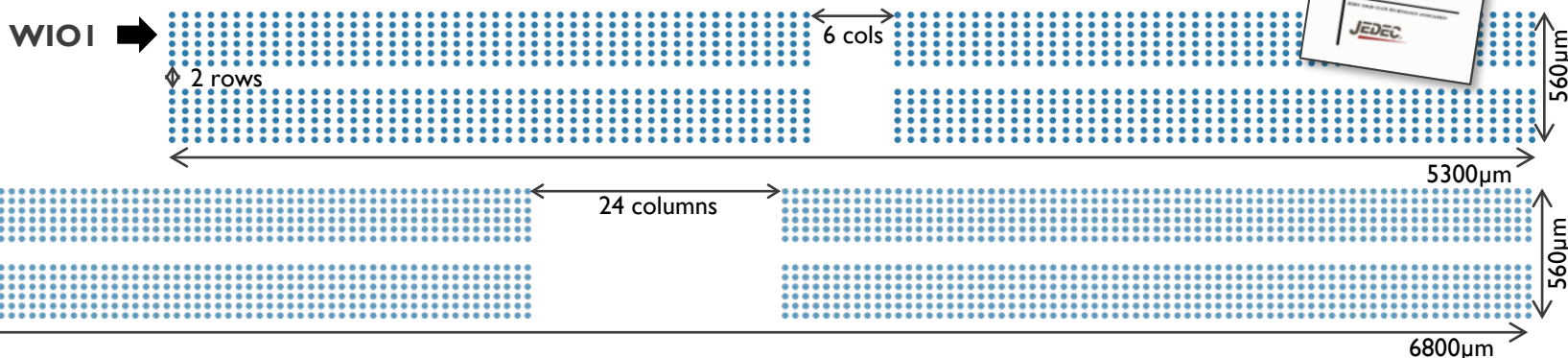
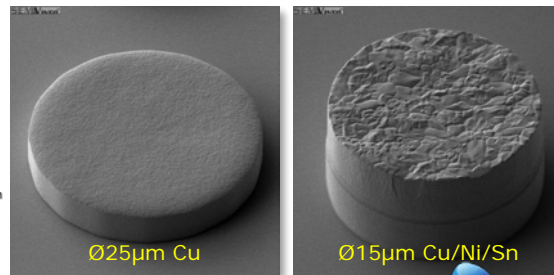
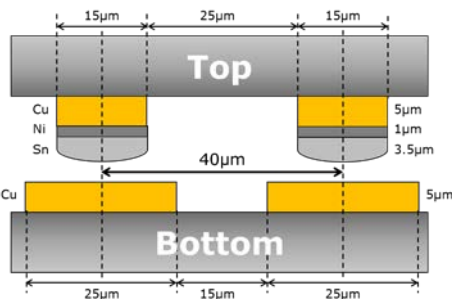
# What Do We Want To Probe?

### Micro-Bump Probe Targets

- imec's PoR @40 $\mu$ m pitch
- Today's advanced industry practice

### Wide-I/O Micro-Bump Arrays

- WIO1: 1,200 micro-bumps @50/40 $\mu$ m pitch
- WIO2: 1,752 micro-bumps @40/40 $\mu$ m pitch



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### 3.VORTEX-2 TEST SYSTEM

# Vortex-2 Test System



**Vortex-2/2**

- micro-bump probing
- parametric testing

**MHU**

wafer  
loader

**Vortex-2/1**

- low-leakage  
parametric testing

### 3.VORTEX-2 TEST SYSTEM

# Vortex-2: In-Line in imec's Fab-2





# Cascade Microtech CM300 Probe Station

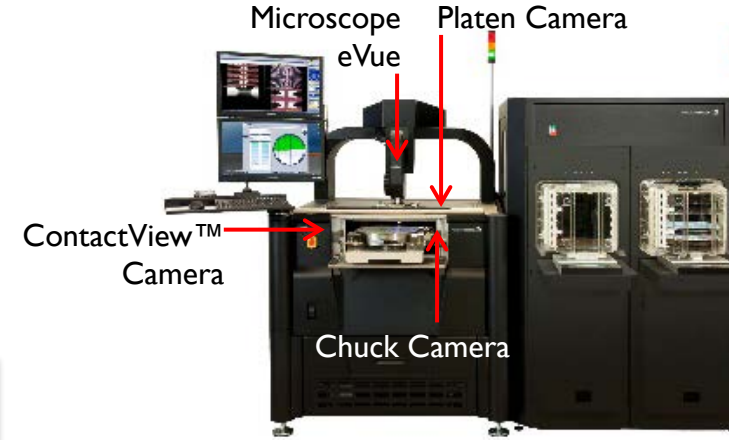
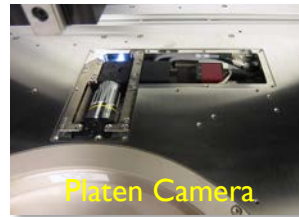
## ■ Wafer Handling

- Full-automatic wafer loader (200/300mm)
- Manual loading of tape frames

## ■ Thermal Control System: -60...+200 °C

## ■ Four Cameras

- ~~(1) eVue~~ ↓ (3) Chuck ↑
- (2) Platen ↓ (4) ContactView™ →

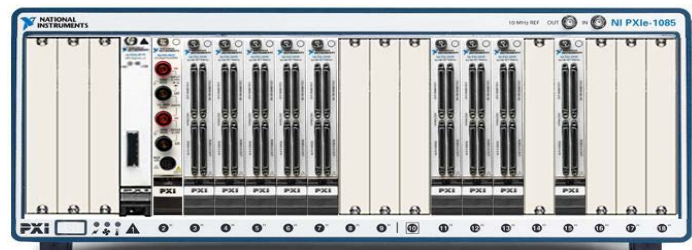
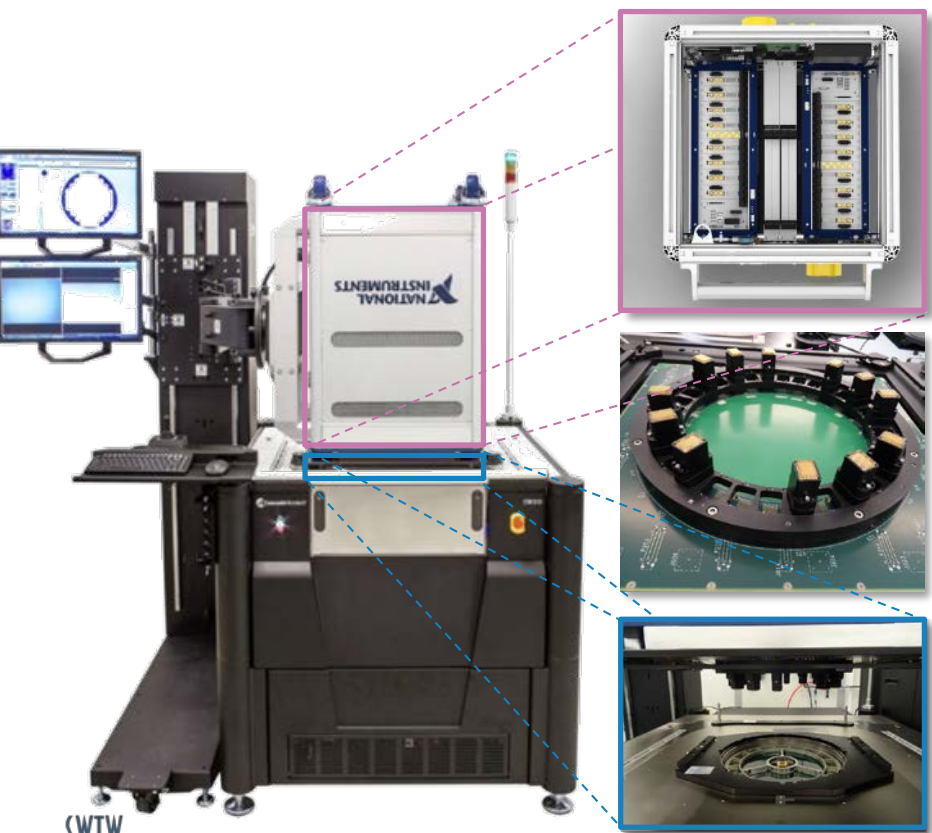


## ■ Microscope Bridge Removed for Test Head

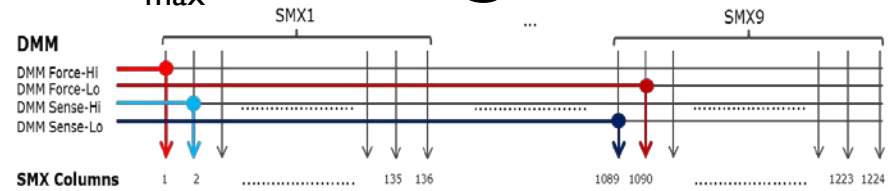
- Probe alignment with Platen and Chuck cameras only
- Chuck needs to move between 'Align' and 'Probe' positions



# National Instruments Semiconductor Test System

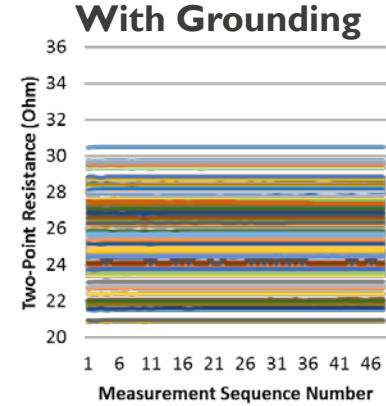
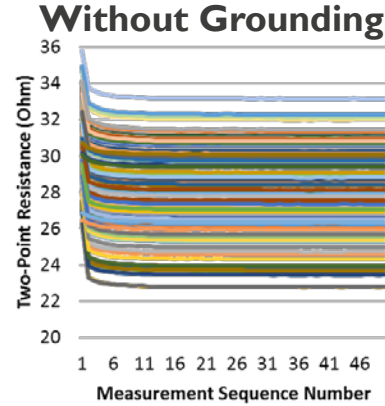


- PXI Rack: programmable Switch Matrix
  - 4 input rows driven by DMM
  - $9 \times 136 = 1,224$  output columns
- Two - and four-point  $R$  measurements
  - $R_{\max} = 1,000 \Omega @ 100 \text{ meas/second}$



# Grounding the FET-Based Switch Matrix

- Wide-I/O Switch Matrix is composed of nine concatenated switch modules
  - $9 \times (4 \times 136) = 4 \text{ rows} \times 1,224 \text{ columns}$
- NI's PXI-2535 FET-based SMX
  - Benefits
    - Low cost and unlimited life-time
    - All 544 switches can be "on"
  - Drawbacks
    - Significant leakage current
    - Charge injection during power-up



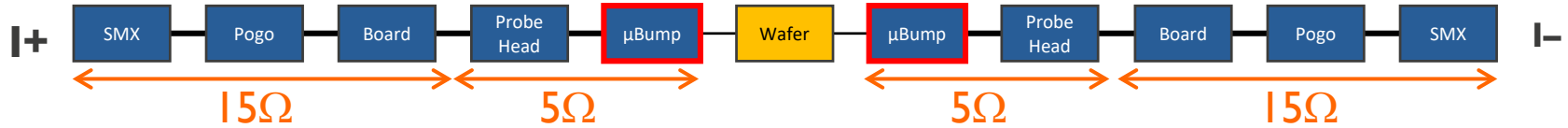
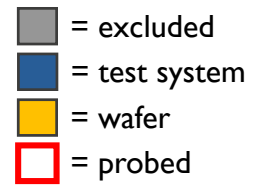
- NI knows issue (manual, website\*), but leaves fix to user
  - We suggested programmable GND as feature in new NI SMX modules
- For now, we implemented a prog'able GND from probe card into SMX

**Caution** During chassis power up, the row and column connections may produce a charge injection.



\* NI website "Why do I get Incorrect Measurements when using the PXI-2535 or PXI-2536?"

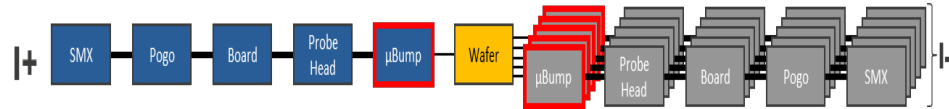
# Measurement Routines and Parasitics



## 1. Probe-Check

- All probes shorted

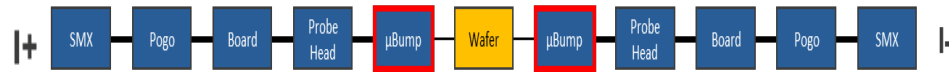
$$R_{\text{parasitic}} \approx 20\Omega$$



## 2. Two-Point

- Micro-bump daisy-chain

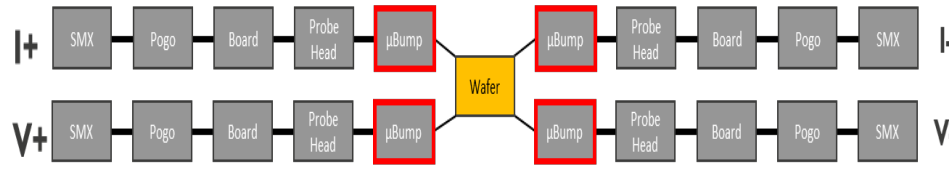
$$R_{\text{parasitic}} \approx 40\Omega$$



## 3. Four-Point

- Requires four probed micro-bumps

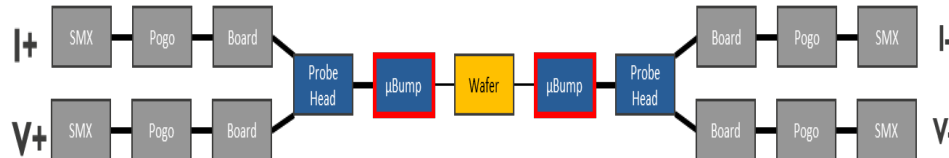
$$R_{\text{parasitic}} \approx 0\Omega$$



## 4. Pseudo Four-Point

- Requires two channels per probe tip

$$R_{\text{parasitic}} \approx 10\Omega$$

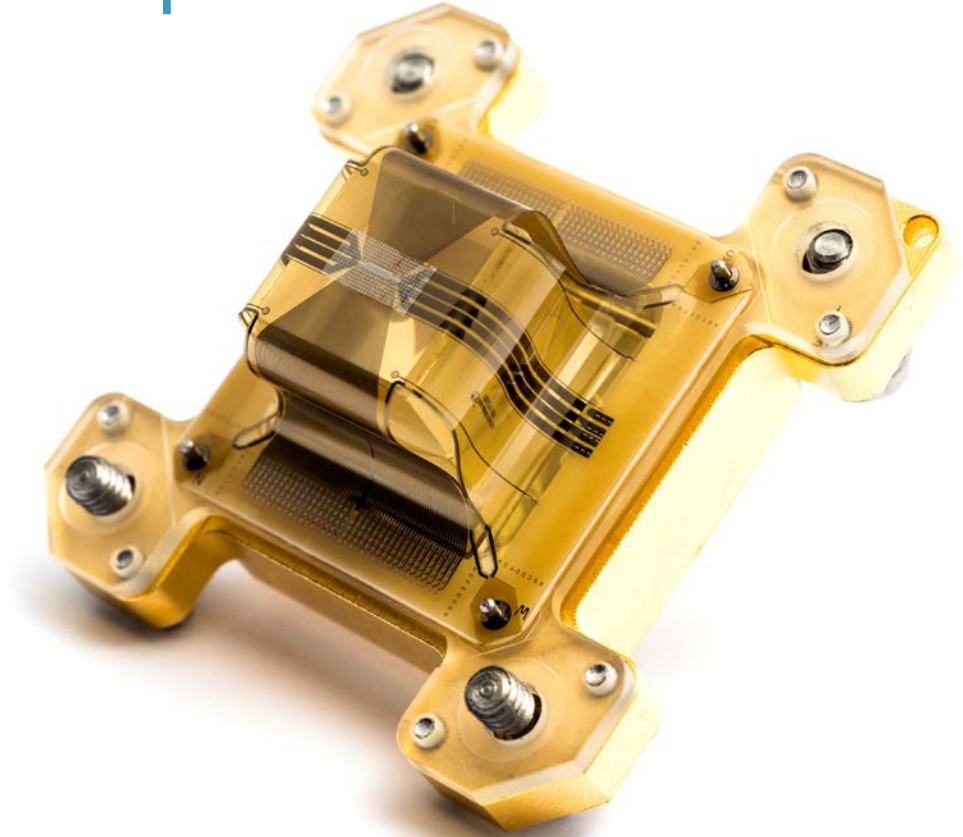
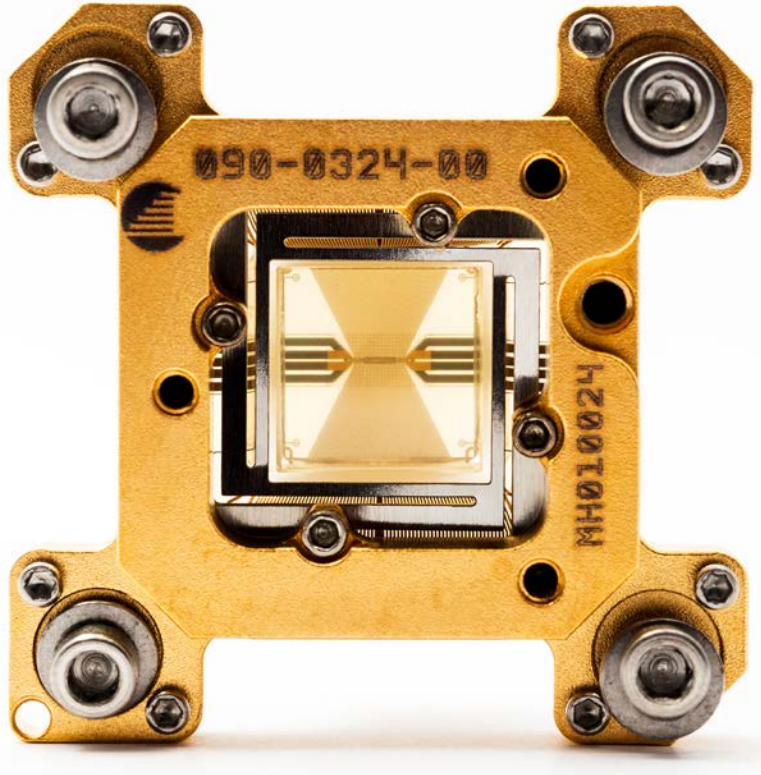


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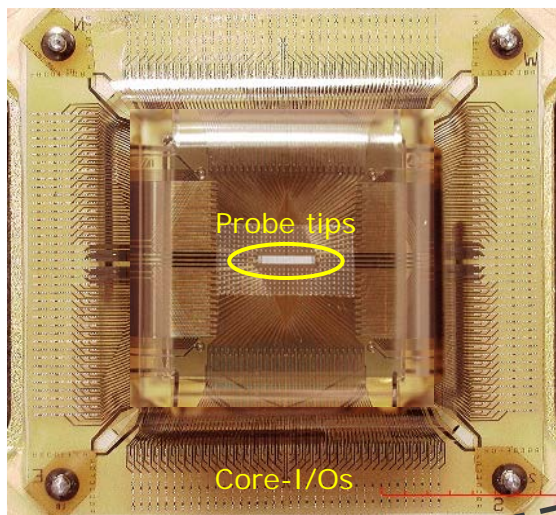
## 4. PROBE TECHNOLOGY

# Pyramid<sup>®</sup> Rocking Beam Interposer Probe Cores

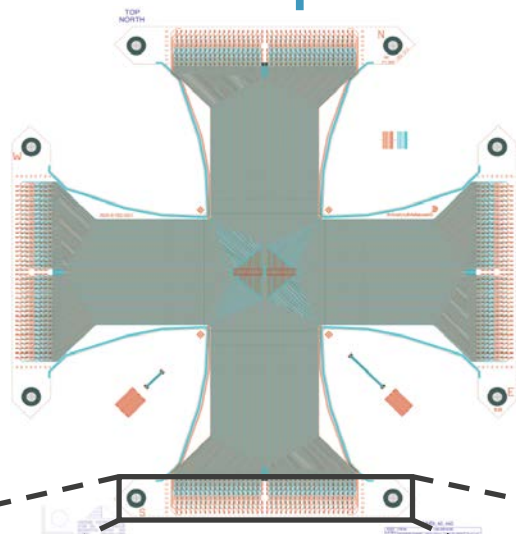


## 4. PROBE TECHNOLOGY

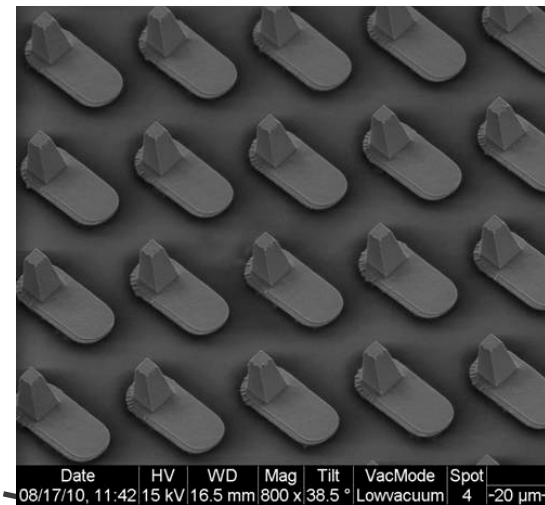
# From Core-I/O to Probe Tip



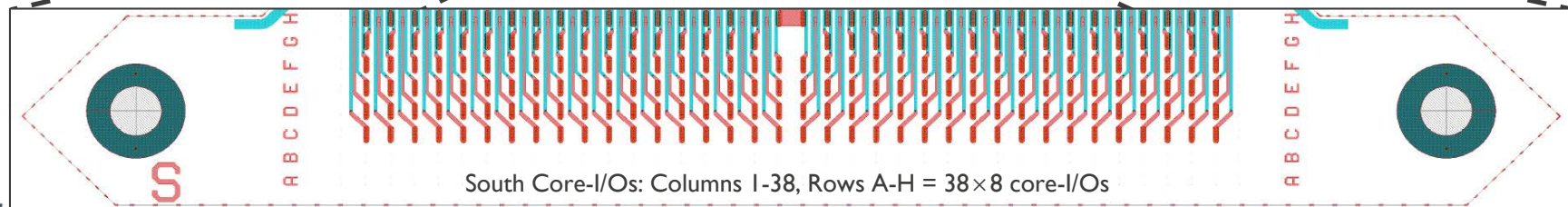
Pyramid Probe® RBI MSI-HD Probe Core with  $4 \times (38 \times 8) = 1,216$  core-I/Os



Probe Core space transformer layout from core-I/Os to probe tips;  $R_{\text{parasitic}} \approx 5 \Omega$



RBI MEMS-type probe tips; micro-scrub with force  $\leq 1$  gf/tip with tip heel of  $6 \times 1 \mu\text{m}^2$



South Core-I/Os: Columns I-38, Rows A-H =  $38 \times 8$  core-I/Os

# Presentation Overview

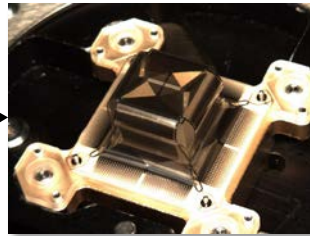
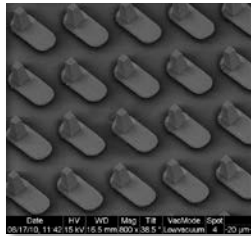
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# Automatic Test Generation Inputs

- Test System Description look-up table

- Per line : probe number; core-I/O; pogo block/pin; switch matrix/column
- Example: 3; SH02; S13\_H08; SMX5\_COL14



Card Name	IMEC-36
Core Type	WIO2-1ch
Banks	1
Rows	6
Columns	73
Pitch	40
Rec. OT	150
Max OT	150
Gap Row	0
Gap Col	0

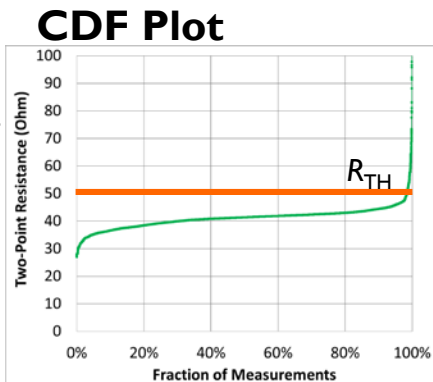
PROBE	CORE IO	POGO PIN	SMX_COL
1	WH23	S19_G05	SMX7_COL113
2	SD02	S13_M06	SMX5_COL86
3	SH02	S13_H08	SMX5_COL14
4	SD03	S13_M05	SMX5_COL90
5	SH03	S13_H07	SMX5_COL10
6	SD04	S13_M04	SMX5_COL94
7	SH04	S13_H06	SMX5_COL6
8	SD05	S13_M03	SMX5_COL98
9	SH05	S13_H05	SMX5_COL12
10	SD06	S13_M02	
11	SH06		

- Probe Core Description

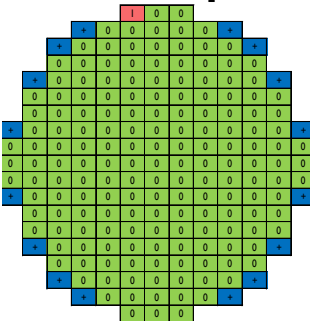
- Key parameters, incl. probes layout and recommended/max OT

# Many Test Results: Data Abstraction & Visualization

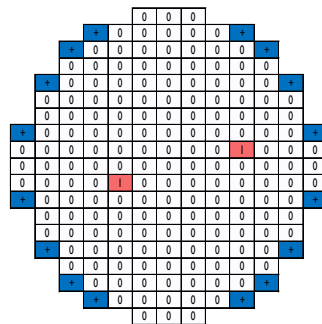
- Individual and aggregate results
- $R_{MAX}$  fixed by meas.mnt range
- $R_{TH}$  determined with CDF plot



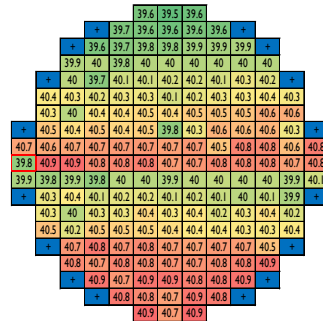
## Wafer Maps



#Opens:  $R > R_{MAX}$

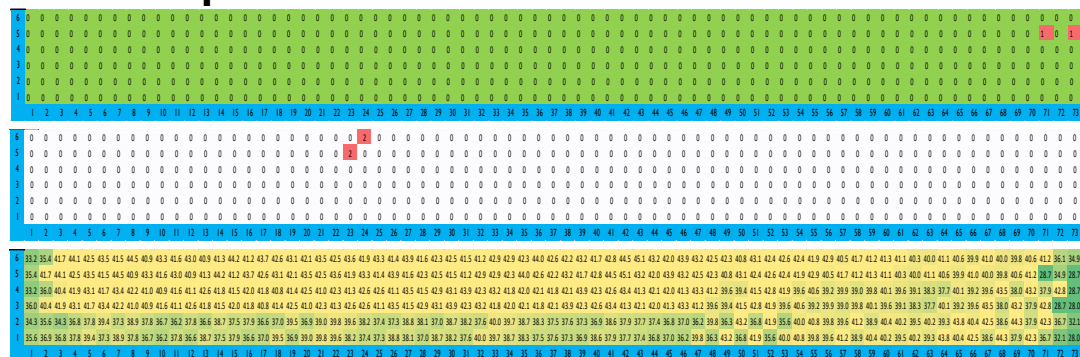


#Fails:  $R_{TH} < R \leq R_{MAX}$

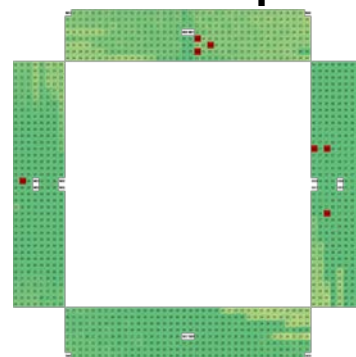


Average:  $R_{AVG}$

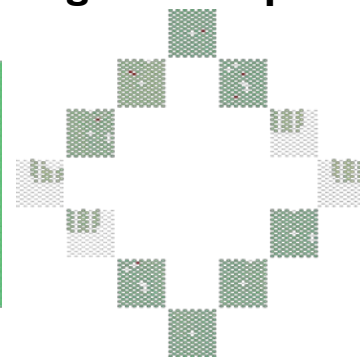
## Probe Maps



## Core-I/O Map



## Pogo-Pin Map



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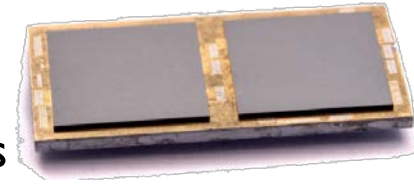
# imec Test Chip Designs with Micro-Bumps

## BMB: Blanket Micro-Bump

- All micro-bumps shorted by blanket Cu
  - Arrays: 50/50 $\mu\text{m}$  pitch, WIO1, WIO2
  - Banks with 0/1/2 dummy rings
- 9,421,272 functional micro-bumps/wafer

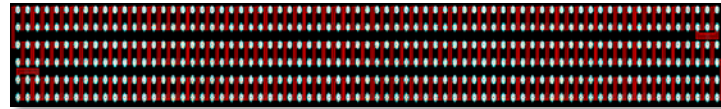
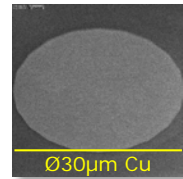
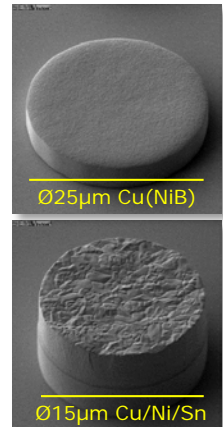
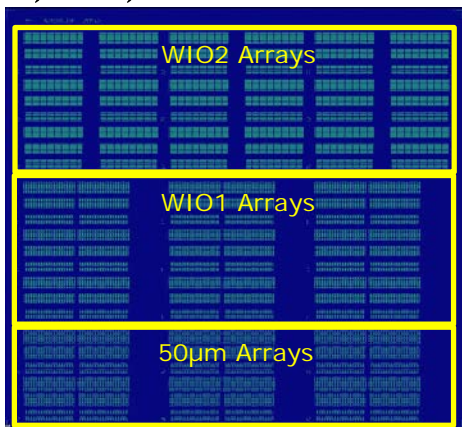
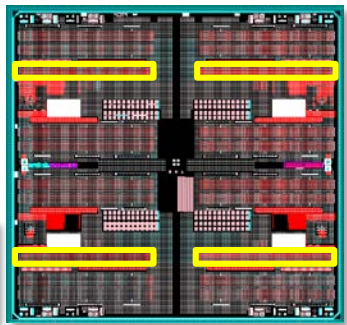
## Vesuvius-2.5D

- WIO1: 1,200 bumps
- 40 daisy-chains of 30 micro-bumps each



## PTCU/W: Processing Test Chips

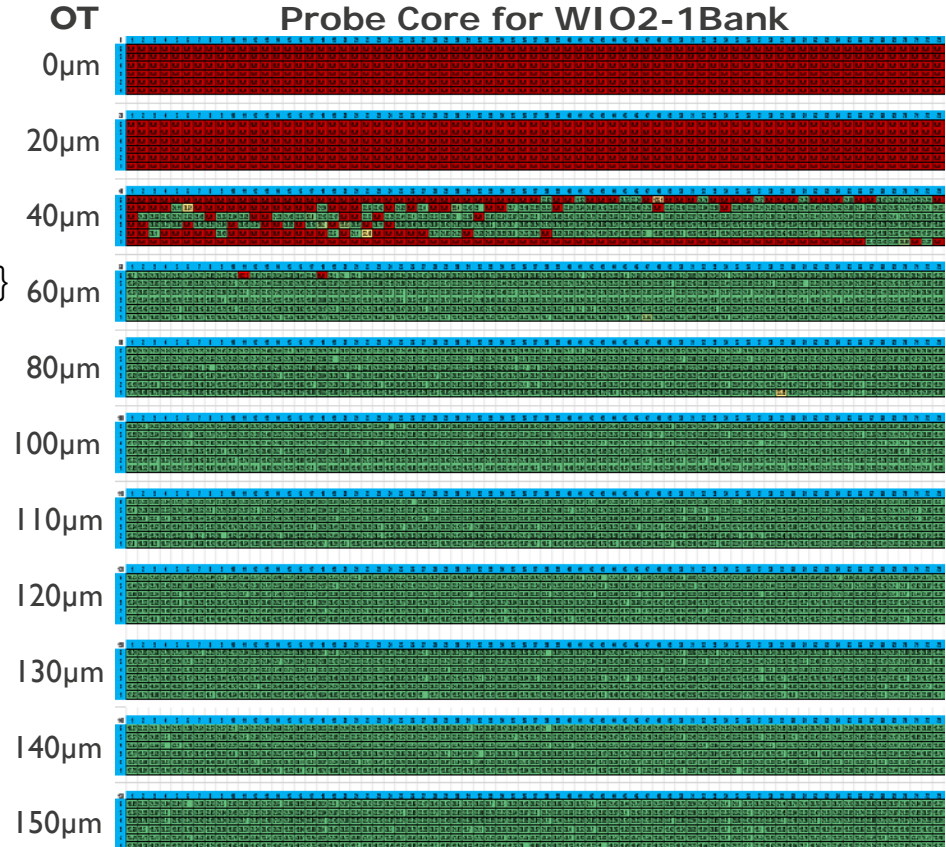
- WIO2 - I bank: 438 micro-bumps
- Embedded micro-bumps: zero height
- Micro-bumps pairwise connected through MI in diagonal fashion



## 6. EXPERIMENTAL RESULTS

# Incoming Inspection on Blanket Wafer

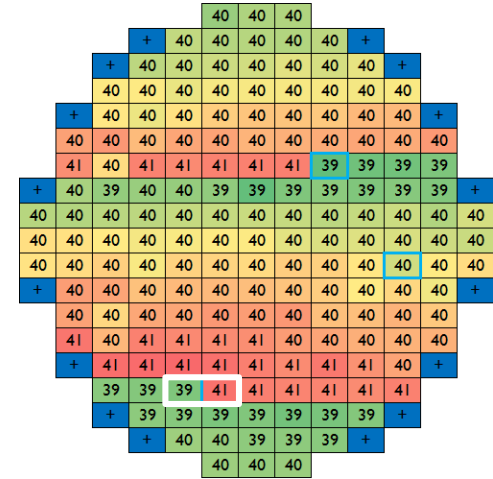
- Increase over-travel from 0 to  $OT_{max}$
- Perform 'Probe Check' routine:  
for all probes  $p \in P$  do {  
    two-point  $R$  measurement  $p$  vs.  $P \setminus \{p\}$   
}
- Determine
  - Open probes, if any:  $R > R_{MAX}$
  - FtL: First-to-Last OT; here  $40\mu m$
  - Recommended OT; here  $100\mu m$ 
    - Too low: poor contact
    - Too high: reduced lifetime



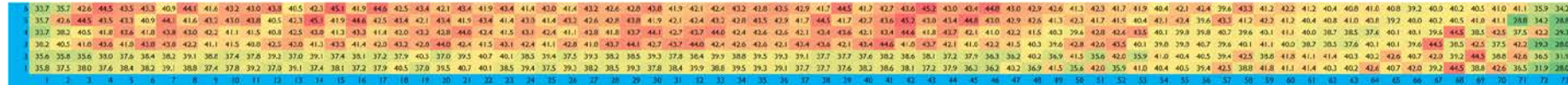
## 6. EXPERIMENTAL RESULTS

# Probe Tip Cleaning

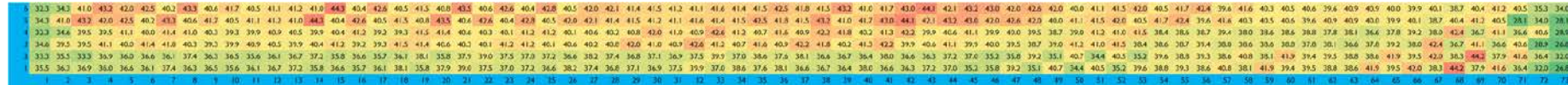
- Recommended cleaning set-up
  - Substrate : ITS Probe Lapping Film, 1  $\mu\text{m}$  grit particle size
  - Recipe : 60% of probing over-travel, 10 touch-downs
  - Interval : After 50 touch-downs



Before Tip Cleaning

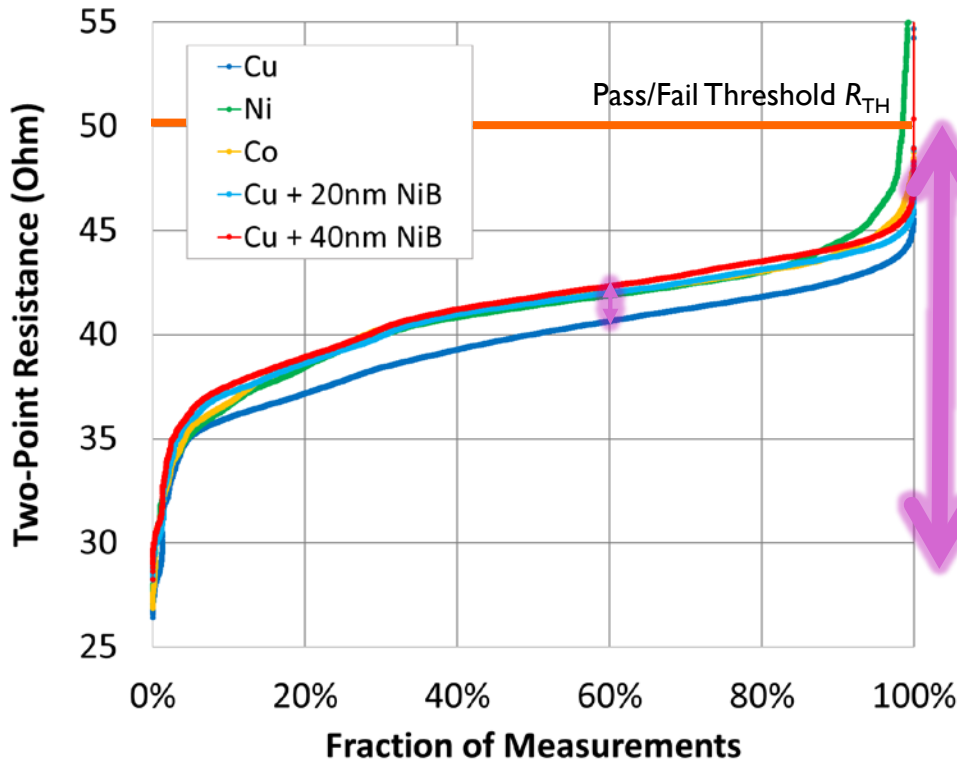


After Tip Cleaning



## 6. EXPERIMENTAL RESULTS

# Contact Resistance Dependent on Bump Metallurgy

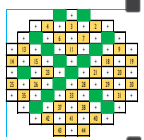


- Sample size: 20,900 – 37,620 measurements per wafer
- Pass/Fail threshold  $R_{TH}$  set at 50  $\Omega$
- Large variation: due to parasitic  $R$  in test system and probe core
- Small variation: micro-bump metallurgy
  - D05: Cu
  - D09: Ni
  - D02: Co
  - D14: Cu +20nm NiB
  - D09: Cu +40nm NiB

# Probe-To-Pad Alignment (PTPA) Accuracy

- **PTPA Accuracy:** determined by (1) probe station and (2) probe core
  - Measure probe-mark errors in all four corners of micro-bump array

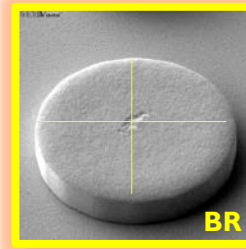
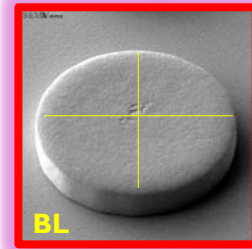
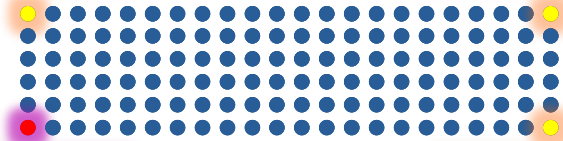
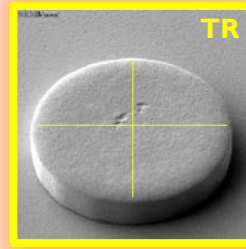
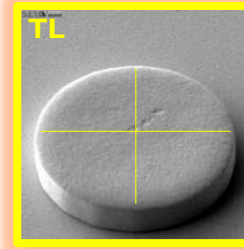
## 1. Probe Station Accuracy



- Equals error of BL probe mark, as BL tip is main probe training location
- Error is chuck-position dependent

## 2. Probe Core Accuracy

- Translate errors such that BL = (0,0)
- Errors other corners due to probe core
- These errors are chuck-pos independent

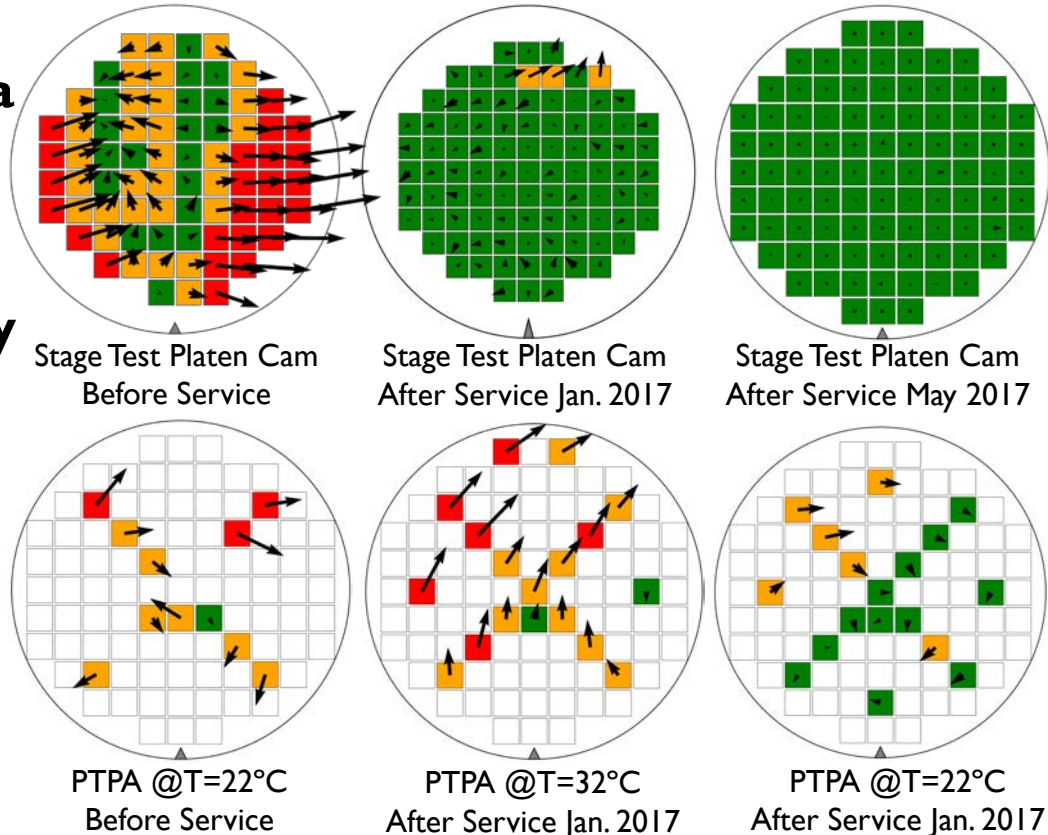




## 6. EXPERIMENTAL RESULTS

# Probe Station's PTPA Results

- **Cannot Use Top-View Camera**
  - No microscope bridge
  - Probe cores 'non see-through'
- **Platen + Chuck Cameras Only**
  - 'Align' ↔ 'Probe': chuck moves
  - Rely on Compensation Matrix
- Compensation Matrix recalibrated in Jan and May 2017
- **Thermal Control** required for accurate PTPA

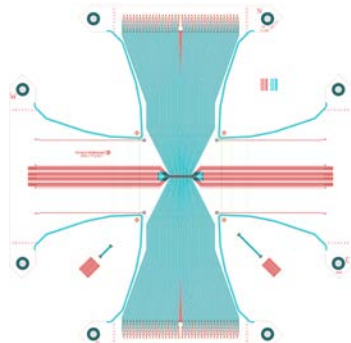


## 6. EXPERIMENTAL RESULTS

# Probe Cores' Grid Accuracy Results

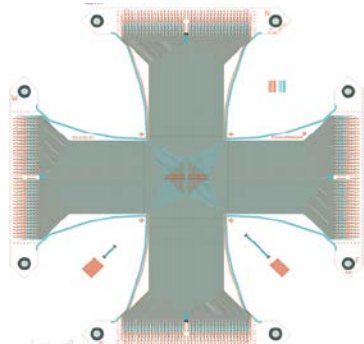
**Legend**  
 — = Ideal  
 — = Actual

### WIO2-1Bank

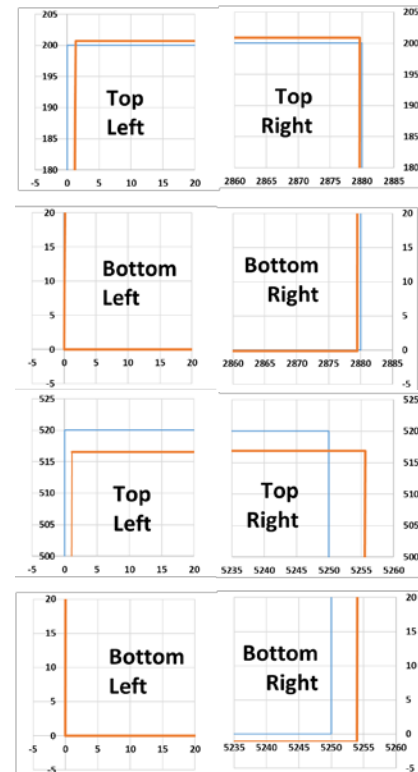


Corner	Ideal ( $\mu\text{m}$ )		Actual ( $\mu\text{m}$ )		Error ( $\mu\text{m}$ )		Relative Error	
	x	y	x	y	x	y	x	y
BL	0.00	0.00	0.00	0.00	0.00	0.00	0.00%	0.00%
BR	2880.00	0.00	2879.47	-0.12	-0.53	-0.12	-0.02%	+0.06%
TR	2880.00	200.00	2879.61	200.88	-0.39	0.88	-0.01%	+0.44%
TL	0.00	200.00	1.33	200.71	1.33	0.71	-0.05%	+0.35%

### WIO1-4Bank

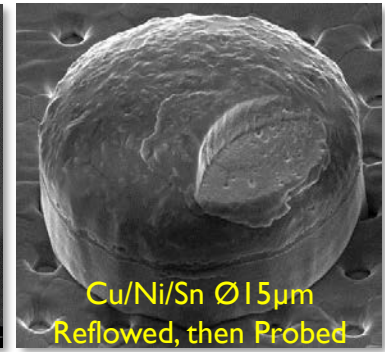
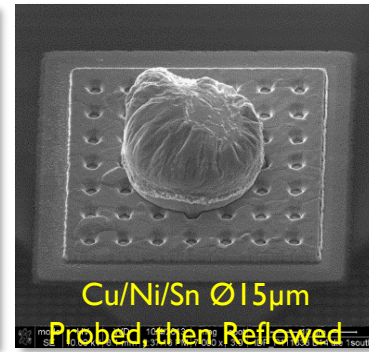
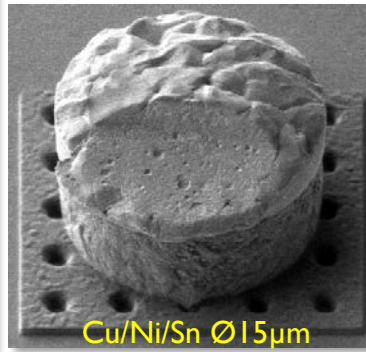
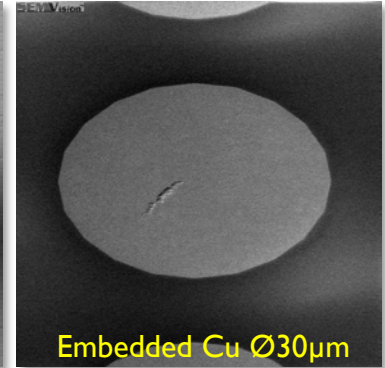
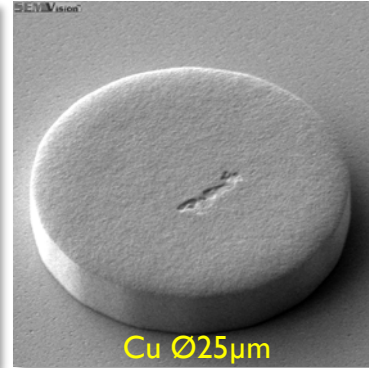
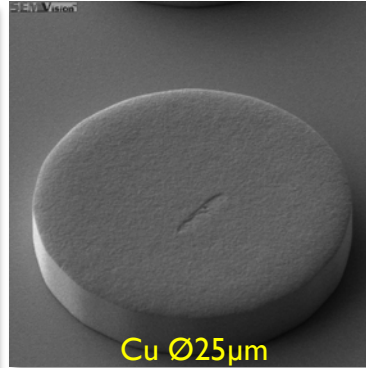
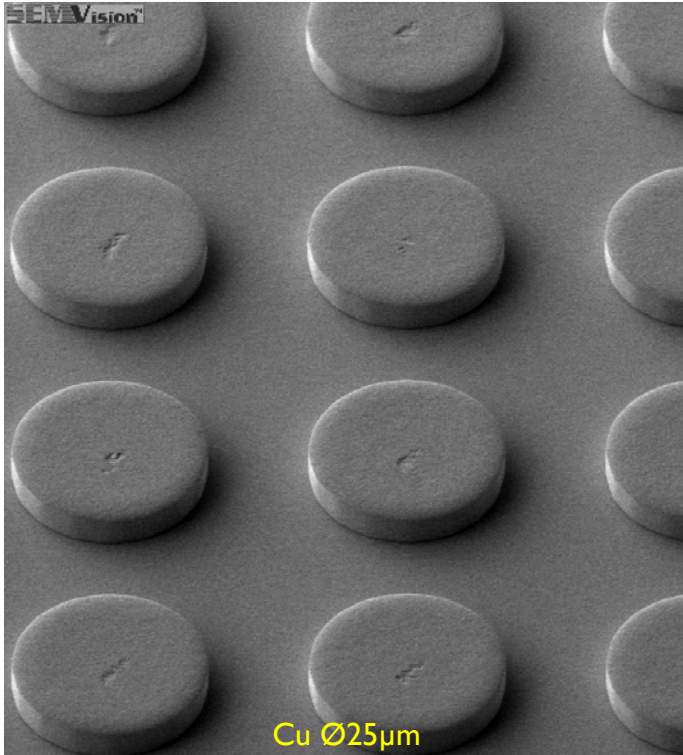


Corner	Ideal ( $\mu\text{m}$ )		Actual ( $\mu\text{m}$ )		Error ( $\mu\text{m}$ )		Relative Error	
	x	y	x	y	x	y	x	y
BL	0.00	0.00	0.00	0.00	0.00	0.00	0.00%	0.00%
BR	5250.00	0.00	5253.93	-0.99	3.93	-0.99	0.07%	-0.19%
TR	5250.00	520.00	5255.65	516.86	5.65	-3.14	0.11%	-0.60%
TL	0.00	520.00	1.13	516.58	1.13	-3.42	0.02 %	-0.66%



## 6. EXPERIMENTAL RESULTS

# Probe Marks on Various Micro-Bumps at 40 $\mu$ m Pitch



## 6. EXPERIMENTAL RESULTS

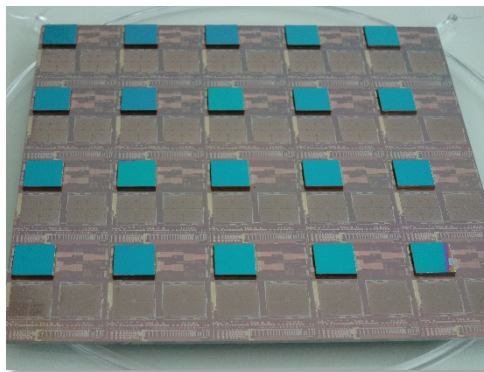
# Probe Mark Impact on Stack Interconnect Yield

### Probe Marks

- On Cu, Co, Ni: very small
- On Sn: can be reflowed away

WIOI Bank	A	B	C	D
Top die probed	✗	✓	✓	✗
Bottom die probed	✓	✓	✗	✗
Interconnect yield	100%	100%	100%	100%
DC resistance $R_{dc}$	32.0 $\Omega$	42.4 $\Omega$	45.0 $\Omega$	33.1 $\Omega$

Vesuvius-2.5D D2W stacks



### Experiment on Vesuvius-2.5D with WIOI-4Banks

- Probed per bank in all four combinations of top/bottom die yes/no probed prior to stacking
- No impact on stack interconnect yield observed

Ch.	DC	Stack 1	Stack 2	Stack 3	Stack 4	Stack 5	Stack 6	Stack 7	Stack 8
A	1	24.8	25.2	25.7	29.3	31.7	34.7	38.7	30.9
A	2	29.7	36.6	37.6	41.0	40.6	106.0	34.7	35.2
A	3	24.7	25.7	27.0	30.5	25.2	25.2	26.3	30.1
A	4	25.8	26.4	27.4	27.6	26.9	27.2	27.6	26.9
A	5	24.0	23.7	25.0	25.0	24.1	26.5	28.1	28.1
A	6	29.4	29.1	30.3	32.3	30.5	33.5	33.7	33.7
A	7	26.8	28.1	27.7	27.6	28.0	27.2	27.9	27.6
A	8	30.4	29.9	32.9	32.1	32.0	32.4	32.1	31.9
A	9	38.2	35.2	40.6	39.1	46.3	42.2	41.6	42.4
A	10	34.3	30.1	33.3	33.3	33.5	35.2	34.7	37.2
B	1	36.3	26.4	39.3	39.4	43.0	46.0	53.7	42.0
B	2	51.3	31.2	44.4	50.3	51.4	53.1	47.3	46.9
B	3	35.8	37.6	38.7	40.4	36.8	36.8	37.5	37.3
B	4	36.8	38.0	39.2	39.6	38.3	39.0	39.5	38.6
B	5	35.3	34.9	36.5	36.5	35.9	36.6	38.7	36.8
B	6	40.4	40.2	43.4	44.1	42.2	44.0	44.8	44.4
B	7	37.9	39.8	39.6	39.3	39.1	38.7	39.8	39.3
B	8	41.5	41.5	44.9	44.2	43.6	43.8	44.5	43.4
B	9	48.2	47.9	51.8	51.5	53.7	54.3	52.9	53.5
B	10	51.1	41.8	44.6	46.1	46.9	51.3	46.3	45.1
C	1	58.4	51.8	78.6	73.5	59.4	98.9	56.0	52.2
C	2	46.5	43.2	44.6	47.4	48.0	49.7	49.4	46.4
C	3	40.0	37.7	41.3	41.1	41.3	41.1	42.7	38.9
C	4	45.1	44.7	49.1	48.2	50.7	51.1	50.0	49.5
C	5	41.0	39.6	43.4	42.6	42.1	41.7	42.4	41.5
C	6	37.5	38.5	38.8	38.8	38.7	38.4	39.0	38.4
C	7	41.1	41.0	42.9	43.6	48.5	44.8	45.3	45.2
C	8	36.9	37.1	38.5	38.2	44.5	38.1	40.1	38.4
C	9	40.0	41.0	42.7	42.4	41.7	41.9	42.4	41.8
C	10	40.2	42.7	42.5	45.3	45.8	40.8	41.5	40.6
D	1	38.4	53.4	67.0	64.5	53.4	62.3	47.8	41.4
D	2	32.4	29.7	32.4	35.4	36.9	35.2	35.9	34.6
D	3	29.5	26.9	29.2	29.0	29.9	30.8	29.5	31.6
D	4	30.8	33.4	38.0	37.5	38.3	39.6	38.3	38.5
D	5	29.8	29.5	31.2	30.7	40.4	30.2	30.5	30.4
D	6	26.1	26.2	27.0	27.9	26.6	26.6	27.1	26.9
D	7	30.1	30.7	30.9	31.8	31.2	33.0	34.7	33.8
D	8	25.7	25.5	26.7	26.5	26.7	26.5	27.5	27.4
D	9	29.5	29.7	30.7	31.0	29.7	30.6	30.4	30.2
D	10	28.8	30.0	31.1	30.7	30.5	30.9	29.9	29.1

[ Marinissen et al. – ITC'14 ]

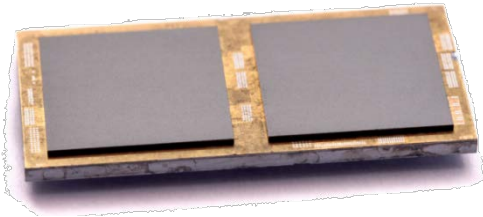
# Presentation Overview

1. Introduction
2. Wide-I/O Micro-Bump Arrays
3. Vortex-2 Test System
4. Probe Technology
5. Test System Software
6. Experimental Results
7. Test Cost Comparison
8. Conclusion

# Cost Modeling for Single-Site Testing

## Cost Comparison

- Case: Vesuvius-2.5D
- Two active dies on top of passive interposer



## Three Scenarios

1. No pre-bond test



2. Extra pre-bond pads



3. Micro-bump probing



Parameter	Interposer	I. No Pre-Bond	2. Extra Pads	3. Bump Probe
		Dies 1+2	Dies 1+2	Dies 1+2
Pre-bond test contacts / die	n.a.	n.a.	only 120	1,200
300mm wafer cost	\$ 700	\$ 3,000	\$ 3,000	\$ 3,000
Die area	200 mm <sup>2</sup>	65.61 mm <sup>2</sup>	66.61 mm <sup>2</sup>	65.61 mm <sup>2</sup>
Gross die / wafer	302	968	953	968
Defect density	0.1 /cm <sup>2</sup>	0.0-1.0 /cm <sup>2</sup>	0.0-1.0 /cm <sup>2</sup>	0.0-1.0 /cm <sup>2</sup>
Die yield	84.52%	100-65.76%	100-65.48%	100-65.76%
Pre-bond fault coverage	n.a.	0%	99%	99%
Pre-bond test time / die	n.a.	0 s	100 s	10 s
Pre-bond probe card cost / die	n.a.	0	0	\$ 0.50
Pre-bond test cost/die	n.a.	\$ 0.00	\$ 5.00	\$ 1.00
Stack interconnect yield	100%	99%	99%	98% ?
Final fault coverage	100%	99%	99%	99%
Final test time / die	1 s	10 s	10 s	10 s

## 7. TEST COST COMPARISON

# 3D-COSTAR Cost Modeling Results

### 1. No Pre-Bond Test

Only acceptable if pre-bond die yield is high

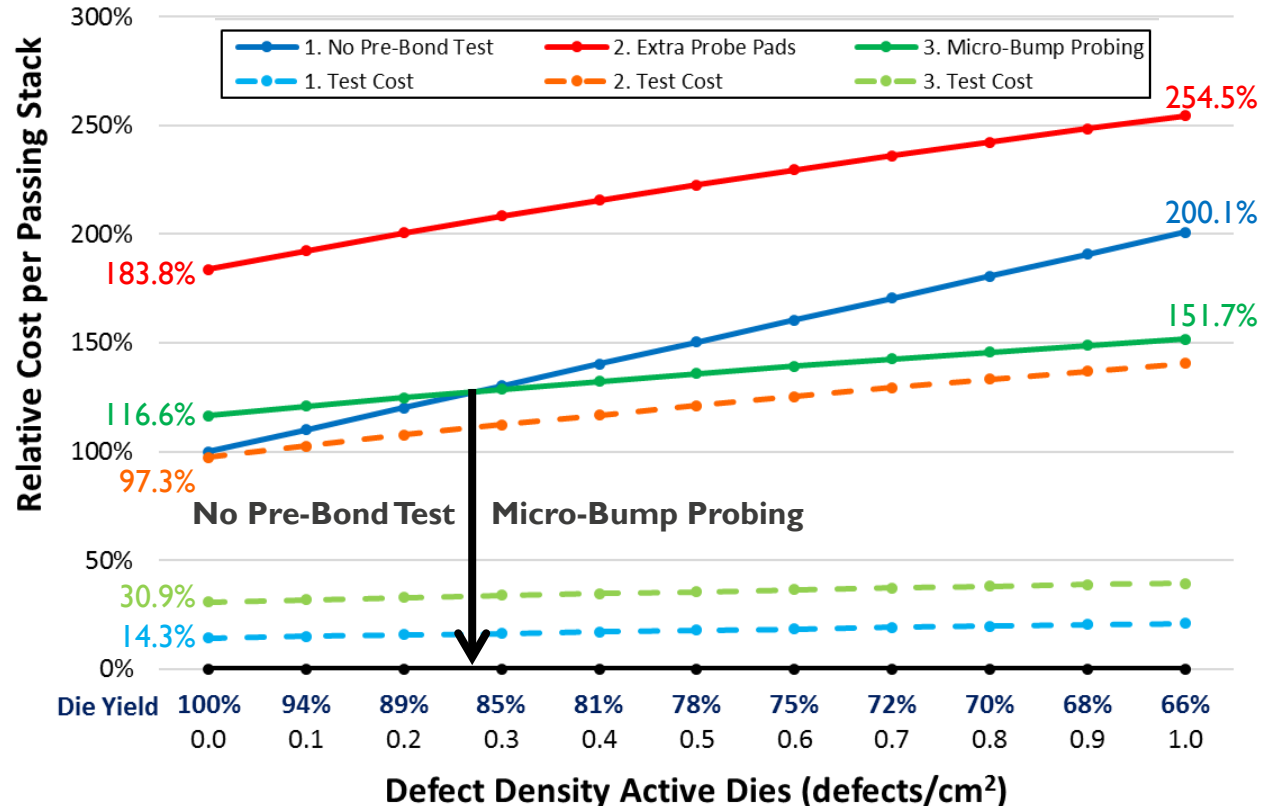
### 2. Extra Pre-Bond Pads

10× test time increase ⇒ test significant cost-add

### 3. Micro-Bump Probing

expensive advanced probe card is minor overall cost contributor

No difference in product quality due to Final Test!



# Presentation Overview

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## 8. CONCLUSION

# Summary

- Unique system for large-array fine-pitch micro-bump probing based on Cascade Microtech CM300
  - At imec routinely used for micro-bump arrays @40/50 $\mu\text{m}$  pitch
  - Temperature control and good calibration required
  - PTPA  $\leq \pm 2.5\mu\text{m}$ : appears sufficient even for 20 $\mu\text{m}$ -pitch micro-bumps
- Cascade Microtech Pyramid<sup>®</sup> RBI probe cards/cores
  - Advanced MEMS-based thin-film probe technology
  - Large arrays down to 40 $\mu\text{m}$  pitch
  - Contact resistance 0.1-2.0 $\Omega$ ; parasitic resistance in space transformer  $\sim 5\Omega$
  - Low force  $\Rightarrow$  Limited probe mark  $\Rightarrow$  No impact on stacking yield observed



# Challenges and Solutions for Micro-Bump Probing

## Challenges

### a. Small Pitch and Diameter

- Pitch =  $40\mu\text{m} \rightarrow 20\mu\text{m}$

### b. Large Micro-Bump Arrays

- WIO1=1200; WIO2=1752; HBM2=4258

### c. Proper Electrical Contact

- Contact resistance  $R_c \leq 5 \Omega$

### d. Probe Marks on Micro-Bumps

- No negative impact on stack yield

### e. Cost of Test

- Economically feasible

## Solutions

- Advanced MEMS-type probe cards
- Accurate, thermally-stable prober
- Large #channels; hard-docking
- Automated data visualization
- Parasitics, over-travel, tip cleaning
- Dependent on bump metallurgy
- Low-force probe cards
- Reflow for soft Sn micro-bumps
- Advanced probes are expensive
- But alternatives are more expensive

## 8. CONCLUSION

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